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Delta phosphorus doped diamond

Like ZnO and GaN semiconductors, the control of diamond's doping for electronics is asymmetric. The p-type doping of diamond by substituting boron for carbon is fairly easy and now technologically mature. In contrast, the n-type conductivity of diamond is still difficult to realize and remains an issue for the fabrication of diamond-based bipolar devices (Fig.1).

Phosphorus is the donor impurity in diamond that gives the highest n-type conductivities. It was shown recently that it contributes to enhance the coherence lifetimes of the famous N-V quantum mitters¹. This breakthrough was reached thanks to progress made in chemical vapor deposition (CVD) for electronics purpose. Indeed, diamond quality has been improved over time with even the possibility to reduce unwanted defects as nuclear spins from the ¹³C isotope together with the control of a low phosphorus doping range ($< 1 \times 10^{17}$ at/cm³)².

From years, my team and I grow n-type phosphorus doped layers in a microwave plasma CVD reactor (MPCVD). Recently, a gas line dedicated to ¹²C isotopically enriched methane was introduced. We are used to control the phosphorus doping from ultra-lightly (n- like) up to heavily (n+ like) phosphorus doped (100) diamond homoepilayers ($\sim 10^{15}$ - 10^{19} at/cm³).

In this work, we develop growth engineering to ensure sharp interface between epilayers (Fig.2). We also evidence a strong reduction of the ¹³C/¹²C ratio by growing phosphorus-doped homoepilayers with ¹²C isotopically enriched methane gas. The control of sharp interfaces together with mastering ¹²C enriched epilayers allow use to grow delta phosphorus doped diamond. By using secondary ion mass spectrometry (SIMS), I will show how ¹²C isotopically enriched methane gas help to understand diamond growth

n ⁺ ultra-thin layer
n ⁻ thin layer
p ⁺ thick substrate

Figure 1 - Example of a stacking structure needed for bipolar devices

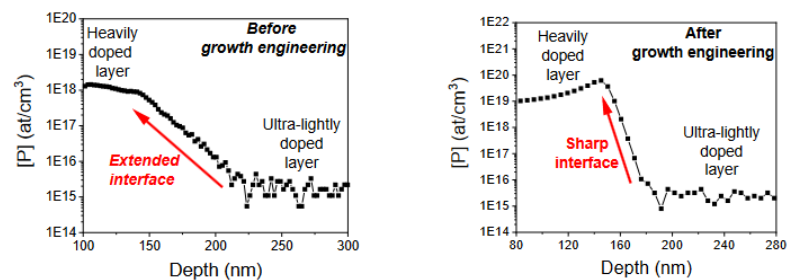


Figure 2 – SIMS profiles showing interface improvement before and after growth engineering

References

1. E.D. Hershleb, *et al. Nature Communications* **10** (2019), 3766.
2. A. Watanabe, *et al. Carbon* **178** (2021) 294.